

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Box Patent Application
 Commissioner for Patents
 P.O. Box 1450
 Alexandria, VA 22313-1450

17302 U.S. PAT. & TM. OFF.
 10/660151
 09/11/03

Re: Inventor(s): Songlin Xu, Thorsten B. Lill, Yeager Arthur Chen, Mohit Jain, Nicolas Gani, Shing-Li Sung, Jitske K. Trevor-Kretz, Meihua Shen, Farid Aboomeri
 Title: PROCESS FOR ETCHING POLYSILICON GATES WITH GOOD MASK SELECTIVITY, CRITICAL DIMENSION CONTROL, AND CLEANLINESS

Transmitted herewith is the patent application identified above, including:

- ☒ Specification, claims and abstract, totaling 21 pages.
☒ Drawings totaling 7 pages, ☒ Formal ☐ Informal.
☒ Executed Declaration and Power of Attorney.
☒ Assignment of the invention to **Applied Materials, Inc.**
☒ Assignment Recordation Cover Sheet
☒ Information Disclosure Statement and Form 1449 along with copies 6 references recited therein

FEE CALCULATION					
Fee Items	Claims Filed	Included With Basic Fee	Extra Claims	Fee Rate	Total
Total Claims	20	-20=		X\$18.00	\$000.00
Independent Claims	3	-3=		X\$84.00	\$000.00
Basic Filing Fee				\$750.00	\$750.00
TOTAL FEES					\$750.00

- ☒ The Commissioner is hereby authorized to charge \$ 750.00 to Deposit Account No. 50-1074.
☒ The Commissioner is hereby authorized to charge any additional fees which may be required, or credit any overpayment to Deposit Account No. 50-1074. A duplicate copy of this transmittal is enclosed.
☒ Please address all future correspondence to:

PATENT COUNSEL
 APPLIED MATERIALS, INC.
 Legal Affairs Department
 P.O. BOX 450A

Santa Clara, CA. 95052

I hereby certify that this correspondence is being deposited with the United States Postal Service as express mail in an envelope addressed to: Commissioner of Patents and Trademarks, Washington, D.C. 20231.

Express Mail Receipt No. EV341110525 US

Date of Deposit SEPTEMBER 11, 2003

Signature Emmanuel

Respectfully submitted,

Robert W. Mulcahy
 Registration No. 25,436